



**UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

SHIMIZU et al

Atty. Ref.: 829-619; Confirmation No. 2644

Appl. No. 10/735,621

TC/A.U. 1763

Filed: December 16, 2003

Examiner: Arancibia, Maureen G.

For: PLASMA CVD APPARATUS, AND METHOD FOR FORMING FILM AND METHOD  
FOR FORMING SEMICONDUCTOR DEVICE USING THE SAME

\* \* \* \* \*

July 20, 2006

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT AFTER FINAL**

Responsive to the Official Action dated March 21, 2006 (for which petition is hereby

made for a one month extension of time), please amend the above-identified application as

follows. *This application places allowable claims in independent form, so that this amendment*

*should be entered and the application is now in condition for allowance given the Examiner's*

*indication of allowable subject matter.*

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